



TECHNOLOGY

Photolithographic Solid-Phase Polymer Synthesis

OVERVIEW

This invention provides an ordered method of forming a plurality of polymer sequences on a porous silica substrate by sequential addition of reagents. The method is accomplished by serially protecting and deprotecting portions of the polymer sequences for addition of other portions of the polymer sequences. Thus one activates and deactivates a portion of the polymers.

Protection includes adding a photoliable protecting group after activation. Such groups can be removed by photolysis in the presence of one or sensitizing agents to unmask a reactive group.

This technology is joint with a publicly traded company and can be offered on a non-exclusive licensing basis. A regular U.S. Patent application is filed.

For additional information, please contact the University of Maryland, College Park, Office of Technology Commercialization. 301 405-3947.

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Additional Information

INSTITUTION

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PATENT STATUS

Issued

LICENSE STATUS

Contact OTC for licensing information

CATEGORIES

- Biomaterials
- Chemical

EXTERNAL RESOURCES

- [US Patent 7,144,700](#)

